

Development and fabrication of graphene Hall probes

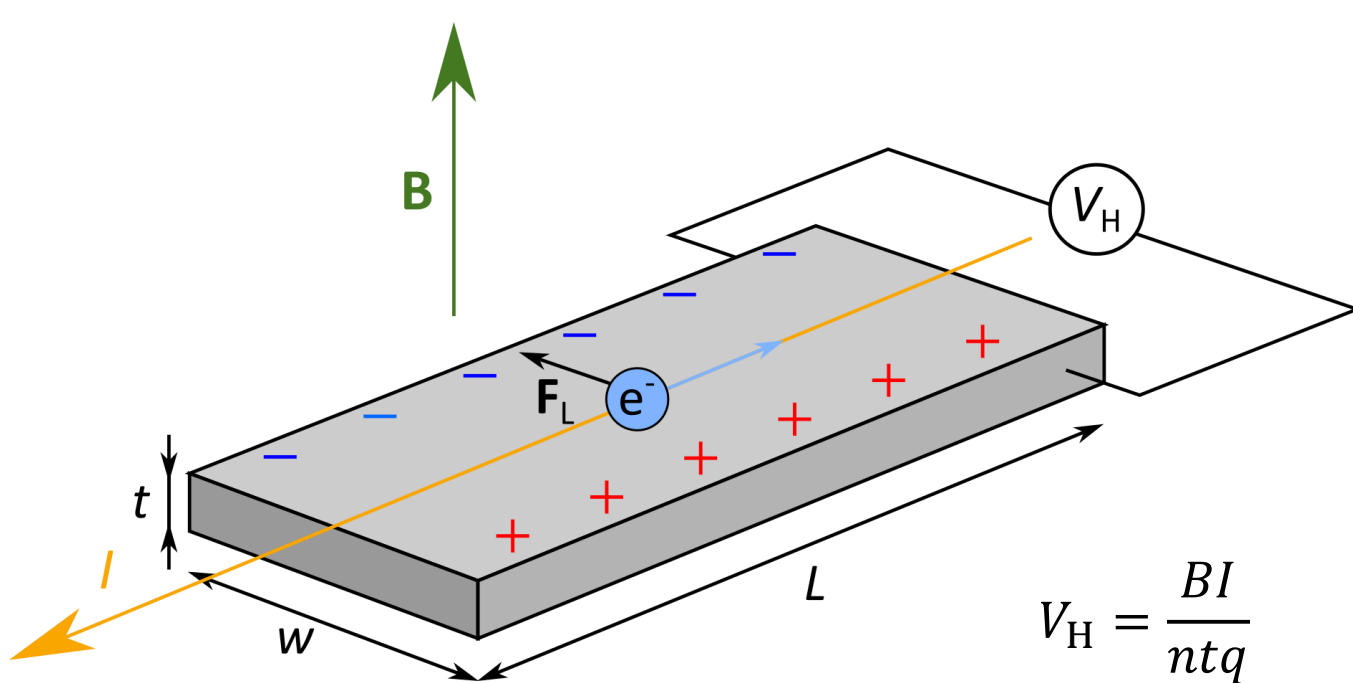
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Hall probes & thesis goals

Hall probe applications:

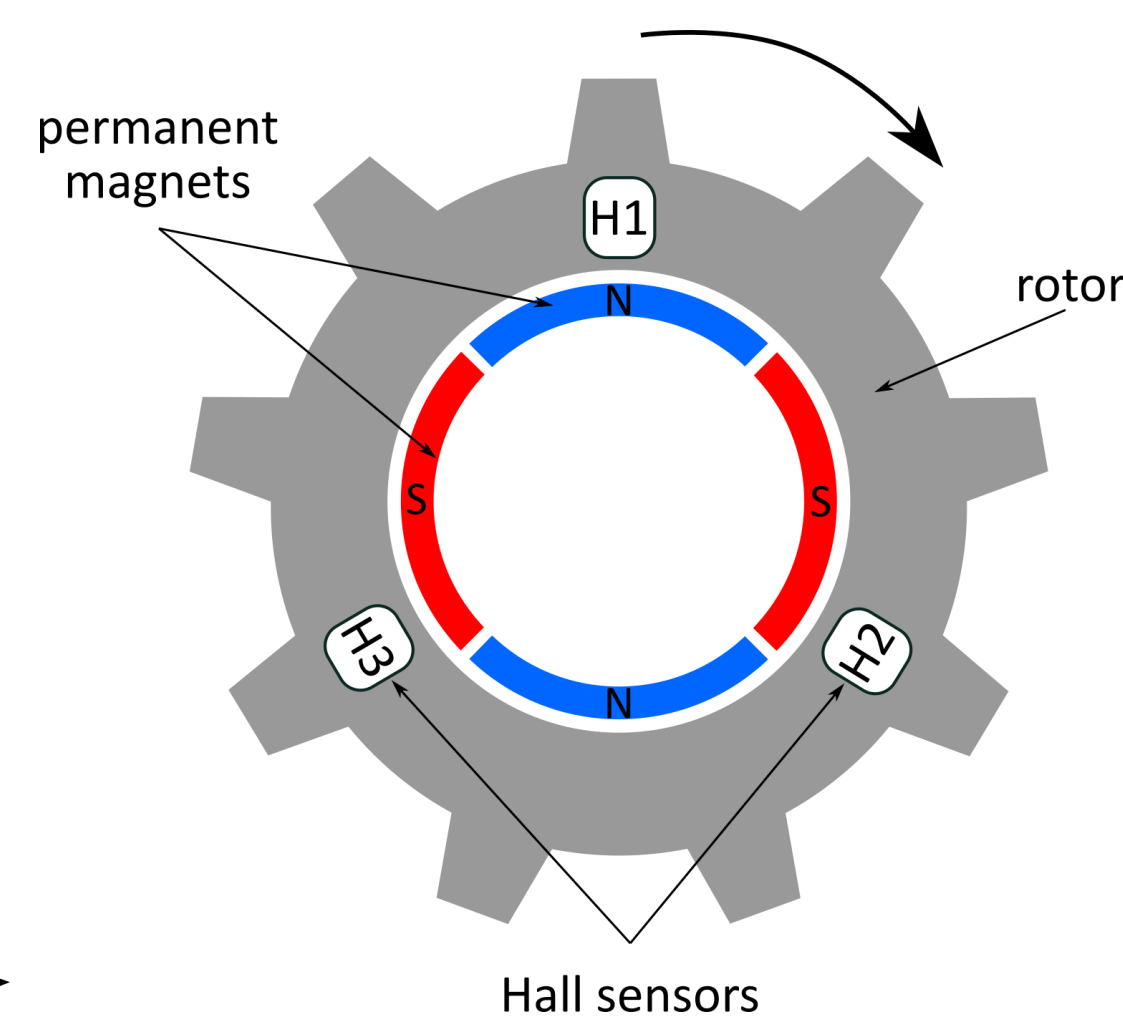
- static & dynamic magnetic field detectors
- current sensing
- speed & directional sensors
- proximity sensors
- ...

Hall effect



$$V_H = \frac{BI}{ntq}$$

V_H ... Hall voltage
 B ... magnetic field
 I ... current
 n ... charge carrier density
 t ... material thickness
 q ... charge



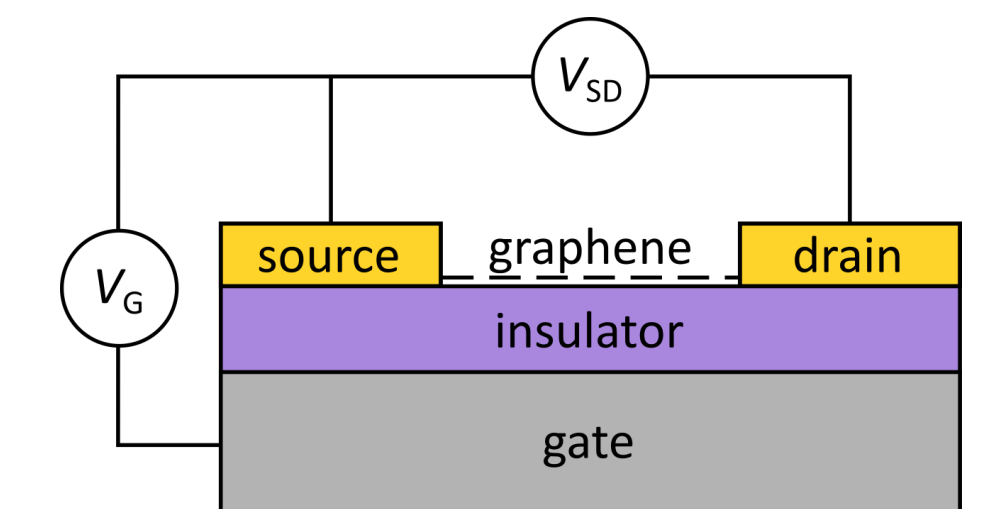
Goals of this work:

- fabrication of graphene Hall probes based on field effect transistors
- testing in varying magnetic fields from room temperature to 200 °C with applied gate voltage

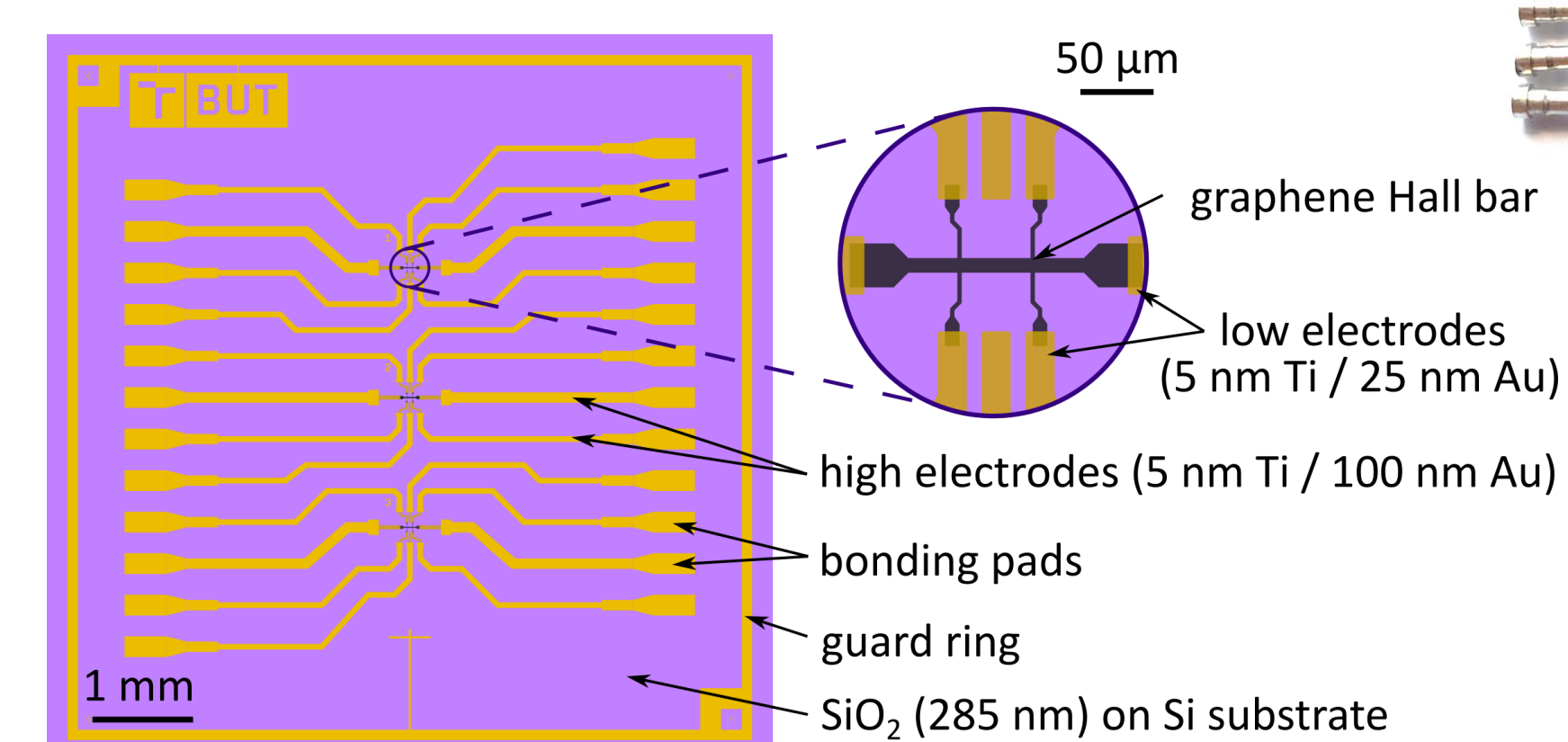
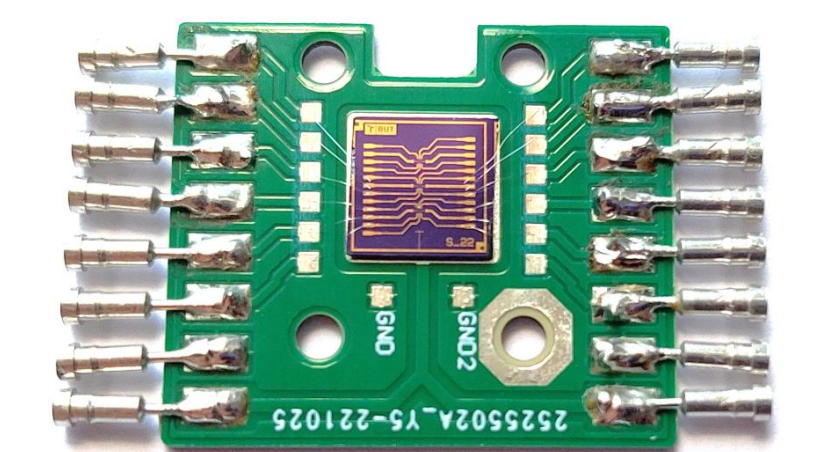
Graphene Hall probe design

➢ field effect transistor arrangement

- enables control of charge carriers in graphene by applying gate voltage
- silicon substrate as a global back gate with 285 nm SiO₂ insulation later



- chip glued and wire bonded on a PCB expander for electronic measurements



Graphene Hall probe fabrication

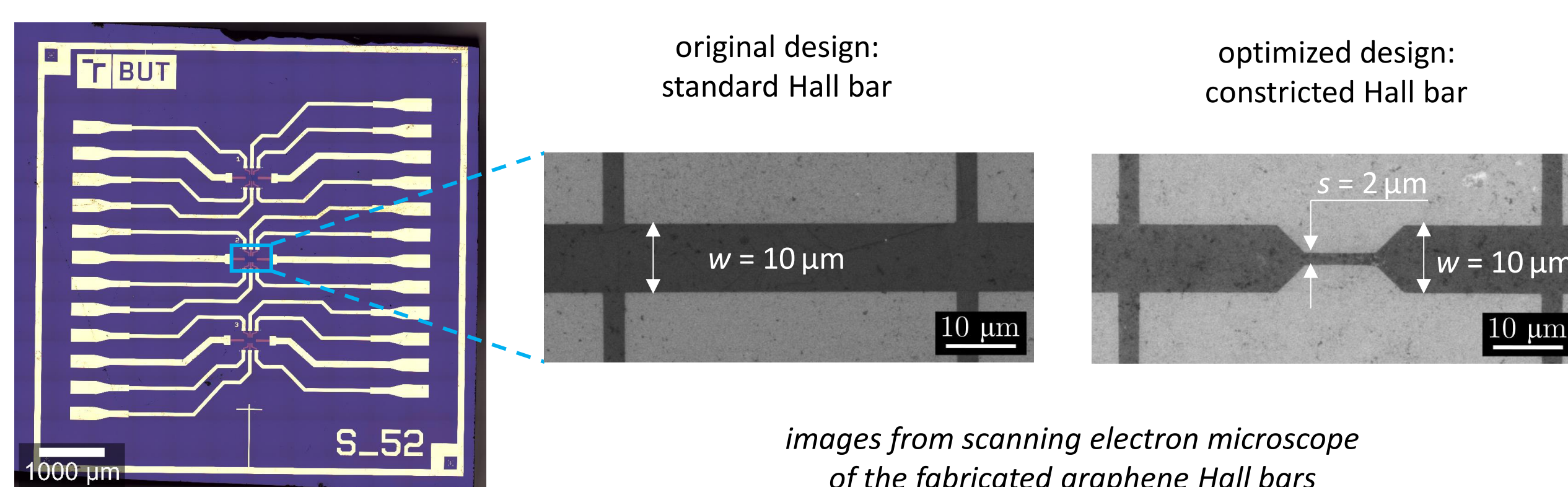
➢ fabrication by standard nano- & micro-fabrication processes

1. patterning of **electrodes** by UV mask lithography & Ti/Au deposition
2. graphene **transfer** onto pre-patterned chips
3. patterning of **graphene Hall bars** by electron beam lithography & plasma etching
4. wire bonding onto chip expanders

➢ optimizations:

- constricted Hall bar
- SU-8 passivation layer

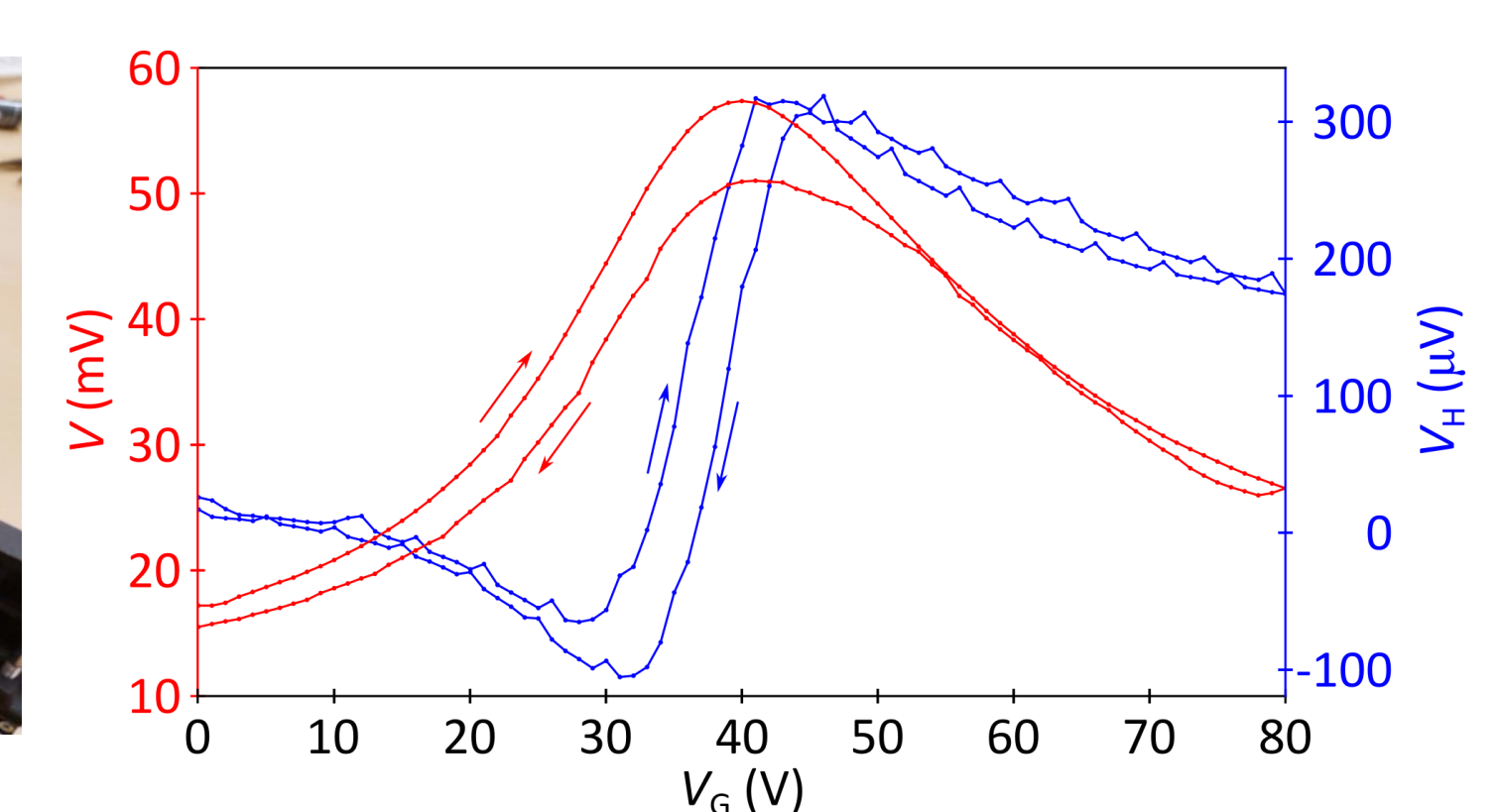
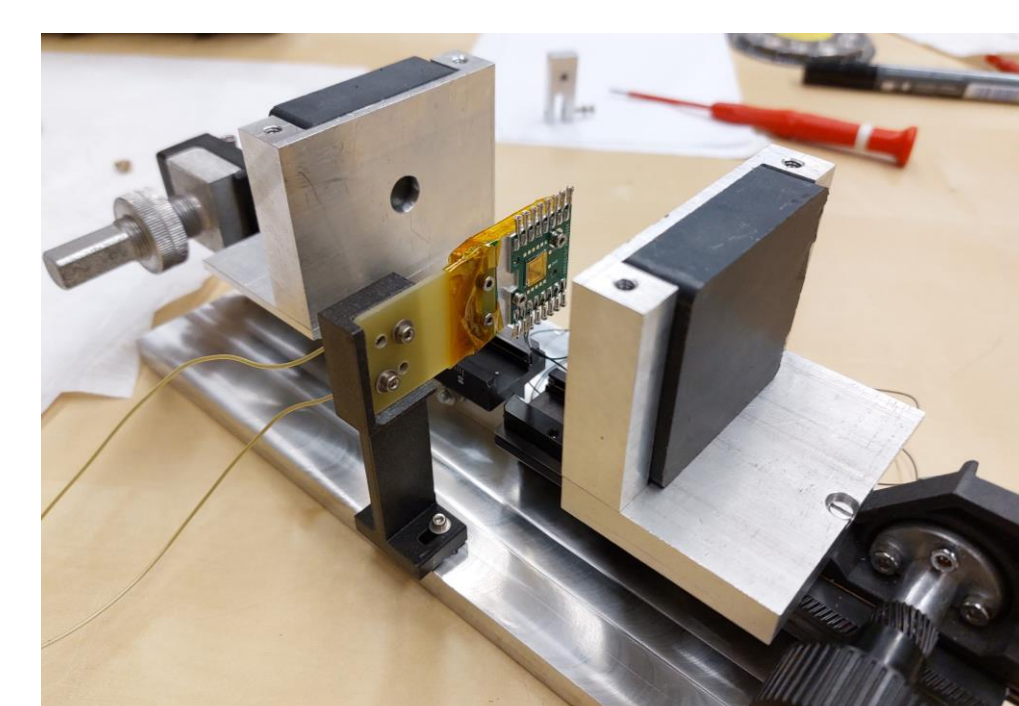
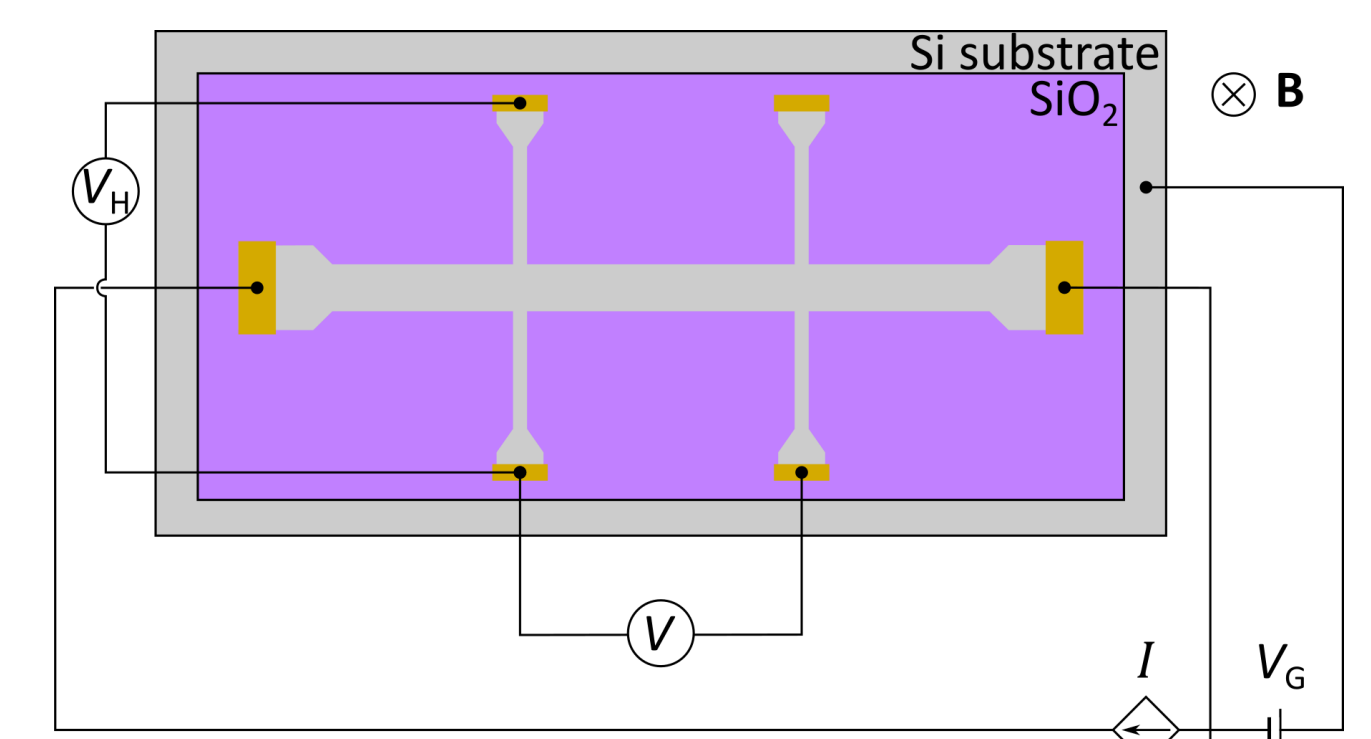
- **quality check** of graphene Hall bars after fabrication by Raman spectroscopy mapping



Hall effect measurement

➢ Experimental setup

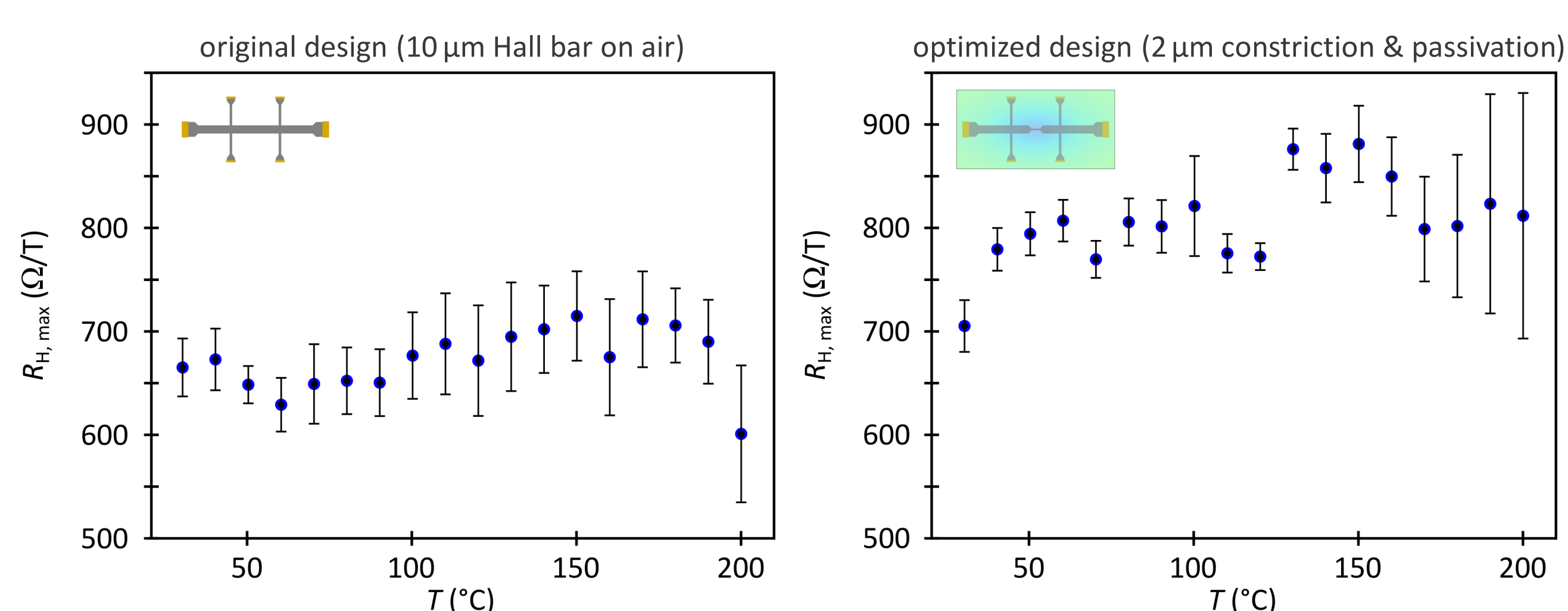
- homogeneous magnetic field from a pair of ferrite magnets
- magnitude & polarity of magnetic field determined by the distance & orientation of the magnets
- simultaneous measurement of the field effect (longitudinal voltage V) & the Hall effect (transverse voltage V_H) in response to applied gate voltage V_G



Sensitivity of the Hall probes

➢ Hall probe sensitivity expressed by the Hall coefficient $R_H = \frac{1}{i} \frac{\partial V_H}{\partial B}$

- Hall elements based on silicon: $R_H \sim (100 - 400) \Omega/T$ ¹
- Hall elements based on graphene: $R_H \sim (1000 - 2000) \Omega/T$
- Hall coefficient of our graphene Hall probes **consistent** across the whole temperature range
- $R_H (200 \text{ °C}) \approx 800 \Omega/T$ about **10x higher** compared to previous graphene Hall probes tested at 200 °C² due to the use of the incorporated field effect transistor



¹ Popovic. *Hall Effect Devices*. London, U.K. 2004.

² CIUK et al. *IEEE Transactions on Electron Devices*. 2019, 66(7). DOI: 10.1109/TED.2019.2915632

Mobility of charge carriers in graphene Hall probes

➢ mobility characterizes how quickly can an electronic device react to electric field

- mobility of silicon at room temperature: $\mu \sim 1000 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$
- mobility of charge carriers in our graphene Hall probes calculated from the simultaneous field effect & Hall effect measurements

